

ABSTRACT

Novel silicon-containing polymers are obtained by
5 copolymerizing a vinylsilane monomer with a compound having
a low electron density unsaturated bond such as maleic
anhydride, maleimide derivatives or tetrafluoroethylene.
Using the polymers, chemical amplification positive resist
compositions sensitive to high-energy radiation and having a
10 high sensitivity and resolution at a wavelength of less than
300 nm and improved resistance to oxygen plasma etching are
obtained.

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